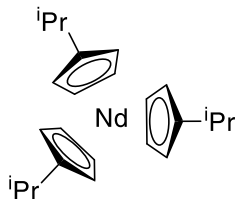


Catalog # 60-6000 Tris(i-propylcyclopentadienyl)neodymium (99.9%-Nd) (REO)



## Technical Notes:

1. Precursor for neodymium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
NdNiO <sub>3</sub>	ALD	160°C	0.7 Torr	Ni( <sup>t</sup> BuAMD) <sub>2</sub> , O <sub>3</sub>	160°C	1

## References:

1. [ACS Appl. Electron. Mater. 2021, 3, 1719](#)